

# Susanne Hoffmann-Eifert

## List of Publications by Year in descending order

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110  
papers

3,580  
citations

147801

31  
h-index

149698

56  
g-index

113  
all docs

113  
docs citations

113  
times ranked

3712  
citing authors

#	ARTICLE	IF	CITATIONS
1	Dielectric, infrared, and Raman response of undoped SrTiO <sub>3</sub> ceramics: Evidence of polar grain boundaries. <i>Physical Review B</i> , 2001, 64, .	3.2	248
2	Control of the morphology of CSD-prepared (Ba,Sr)TiO <sub>3</sub> thin films. <i>Journal of the European Ceramic Society</i> , 1999, 19, 1339-1343.	5.7	171
3	Ferroelectric thin films grown on tensile substrates: Renormalization of the Curie-Weiss law and apparent absence of ferroelectricity. <i>Journal of Applied Physics</i> , 1999, 85, 1698-1701.	2.5	143
4	Realization of Boolean Logic Functionality Using Redox-Based Memristive Devices. <i>Advanced Functional Materials</i> , 2015, 25, 6414-6423.	14.9	127
5	Sr diffusion in undoped and La-doped SrTiO <sub>3</sub> single crystals under oxidizing conditions. <i>Physical Chemistry Chemical Physics</i> , 2005, 7, 2053-2060.	2.8	122
6	Influence of Precursor Chemistry on the Formation of MTiO <sub>3</sub> (M = Ba, Sr) Ceramic Thin Films. <i>Journal of Sol-Gel Science and Technology</i> , 1998, 12, 67-79.	2.4	119
7	Do dislocations act as atomic autobahns for oxygen in the perovskite oxide SrTiO <sub>3</sub> ?. <i>Nanoscale</i> , 2014, 6, 12864-12876.	5.6	118
8	Origin of soft-mode stiffening and reduced dielectric response in SrTiO <sub>3</sub> thin films. <i>Physical Review B</i> , 2002, 66, .	3.2	114
9	Multidimensional Simulation of Threshold Switching in NbO <sub>2</sub> Based on an Electric Field Triggered Thermal Runaway Model. <i>Advanced Electronic Materials</i> , 2016, 2, 1600169.	5.1	95
10	Improved Switching Stability and the Effect of an Internal Series Resistor in HfO <sub>2</sub> /TiO <sub>x</sub> Bilayer ReRAM Cells. <i>IEEE Transactions on Electron Devices</i> , 2018, 65, 3229-3236.	3.0	95
11	Exploiting the switching dynamics of HfO <sub>2</sub> -based ReRAM devices for reliable analog memristive behavior. <i>APL Materials</i> , 2019, 7, .	5.1	94
12	Dopant influence on dielectric losses, leakage behaviour, and resistance degradation of SrTiO <sub>3</sub> thin films. <i>Thin Solid Films</i> , 1997, 305, 66-73.	1.8	87
13	Microstructure of columnar-grained SrTiO <sub>3</sub> and BaTiO <sub>3</sub> thin films prepared by chemical solution deposition. <i>Journal of Materials Research</i> , 1998, 13, 2206-2217.	2.6	87
14	Title is missing!. , 2002, 9, 5-16.		78
15	Growth and Crystallization of TiO <sub>2</sub> Thin Films by Atomic Layer Deposition Using a Novel Amido Guanidinate Titanium Source and Tetrakis-dimethylamido-titanium. <i>Chemistry of Materials</i> , 2013, 25, 2934-2943.	6.7	75
16	Variability-Aware Modeling of Filamentary Oxide-Based Bipolar Resistive Switching Cells Using SPICE Level Compact Models. <i>IEEE Transactions on Circuits and Systems I: Regular Papers</i> , 2020, 67, 4618-4630.	5.4	72
17	Understanding the Coexistence of Two Bipolar Resistive Switching Modes with Opposite Polarity in Pt/TiO <sub>2</sub> /Ti/Pt Nanosized ReRAM Devices. <i>ACS Applied Materials &amp; Interfaces</i> , 2018, 10, 29766-29778.	8.0	71
18	Electrical Conductivity of Epitaxial SrTiO <sub>3</sub> Thin Films as a Function of Oxygen Partial Pressure and Temperature. <i>Journal of the American Ceramic Society</i> , 2006, 89, 2845-2852.	3.8	62

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19	Advanced chemical deposition techniques - from research to production. Integrated Ferroelectrics, 2001, 36, 3-20.	0.7	61
20	Uniting Gradual and Abrupt set Processes in Resistive Switching Oxides. Physical Review Applied, 2016, 6, .	3.8	61
21	Dielectric properties, leakage behaviour, and resistance degradation of thin films of the solid solution series Ba(Ti <sub>1-y</sub> Zr <sub>y</sub> )O <sub>3</sub> . Integrated Ferroelectrics, 1997, 17, 141-152.	0.7	56
22	Space charges and defect concentration profiles at complex oxide interfaces. Physical Review B, 2016, 93, .	3.2	51
23	Influence of charge compensation mechanisms on the sheet electron density at conducting LaAlO <sub>3</sub> /SrTiO <sub>3</sub> -interfaces. Applied Physics Letters, 2012, 100, .	3.3	48
24	Finite-size versus interface-proximity effects in thin-film epitaxial $\text{SrTiO}_3/\text{LaAlO}_3$ bilayers. Physical Review B, 2014, 89, .	3.2	47
25	Relation Between Enhancement in Growth and Thickness-Dependent Crystallization in ALD TiO <sub>2</sub> Thin Films. Journal of the Electrochemical Society, 2011, 158, D6.	2.9	44
26	High temperature conductance characteristics of LaAlO <sub>3</sub> /SrTiO <sub>3</sub> -heterostructures under equilibrium oxygen atmospheres. Applied Physics Letters, 2010, 97, .	3.3	43
27	Defect Control of Conventional and Anomalous Electron Transport at Complex Oxide Interfaces. Physical Review X, 2016, 6, .	8.9	42
28	Transport limits in defect-engineered LaAlO <sub>3</sub> /SrTiO <sub>3</sub> bilayers. Nanoscale, 2015, 7, 1013-1022.	5.6	39
29	Sharp ferroelectric phase transition in strained single-crystalline SrRuO <sub>3</sub> /Ba <sub>0.7</sub> Sr <sub>0.3</sub> TiO <sub>3</sub> /SrRuO <sub>3</sub> capacitors. Applied Physics Letters, 2003, 83, 5011-5013.	3.3	38
30	Thermodynamic Ground States of Complex Oxide Heterointerfaces. ACS Applied Materials & Interfaces, 2017, 9, 1086-1092.	8.0	34
31	Effect of the Threshold Kinetics on the Filament Relaxation Behavior of Ag-Based Diffusive Memristors. Advanced Functional Materials, 2022, 32, .	14.9	33
32	Digital reflection-type phase shifter based on a ferroelectric planar capacitor. IEEE Microwave and Wireless Components Letters, 2001, 11, 407-409.	3.2	32
33	Stoichiometry dependence and thermal stability of conducting NdGaO <sub>3</sub> /SrTiO <sub>3</sub> heterointerfaces. Applied Physics Letters, 2013, 102, .	3.3	32
34	Disentanglement of growth dynamic and thermodynamic effects in LaAlO <sub>3</sub> /SrTiO <sub>3</sub> heterostructures. Scientific Reports, 2016, 6, 22410.	3.3	31
35	Atomic Layer Deposition of Transparent VO <sub>x</sub> Thin Films for Resistive Switching Applications. Chemical Vapor Deposition, 2014, 20, 291-297.	1.3	28
36	Functional graded high-K (Ba <sub>1-x</sub> Sr <sub>x</sub> )TiO <sub>3</sub> thin films for capacitor structures with low temperature coefficient. Integrated Ferroelectrics, 1999, 24, 169-179.	0.7	27

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37	Liquid Injection ALD of Pb(Zr,Ti)O <sub>x</sub> Thin Films by a Combination of Self-Regulating Component Oxide Processes. <i>Journal of the Electrochemical Society</i> , 2007, 154, G262.	2.9	26
38	Growth of ternary PbTiO <sub>x</sub> films in a combination of binary oxide atomic layer depositions. <i>Journal of Applied Physics</i> , 2007, 101, 014114.	2.5	26
39	Growth of Noble Metal Ru Thin Films by Liquid Injection Atomic Layer Deposition. <i>Journal of Physical Chemistry C</i> , 2009, 113, 11329-11335.	3.1	26
40	Utilizing the Switching Stochasticity of HfO <sub>2</sub> /TiO <sub>x</sub> -Based ReRAM Devices and the Concept of Multiple Device Synapses for the Classification of Overlapping and Noisy Patterns. <i>Frontiers in Neuroscience</i> , 2021, 15, 661856.	2.8	26
41	Growth Behavior of Atomic-Layer-Deposited Pb(Zr,Ti)O <sub>x</sub> Thin Films on Planar Substrate and Three-Dimensional Hole Structures. <i>Journal of the Electrochemical Society</i> , 2008, 155, D715.	2.9	25
42	Resistance degradation behavior of Ba <sub>0.7</sub> Sr <sub>0.3</sub> TiO <sub>3</sub> thin films compared to mechanisms found in titanate ceramics and single crystals. <i>Integrated Ferroelectrics</i> , 1998, 22, 83-94.	0.7	24
43	SrTiO <sub>3</sub> thin film capacitors on silicon substrates with insignificant interfacial passive layers. <i>Applied Physics Letters</i> , 2010, 97, 132907.	3.3	24
44	Atomic-Scale Measurement of Structure and Chemistry of a Single-Unit-Cell Layer of LaAlO <sub>3</sub> Embedded in SrTiO <sub>3</sub> . <i>Microscopy and Microanalysis</i> , 2013, 19, 310-318.	0.4	24
45	Resistive Switching of Individual, Chemically Synthesized TiO <sub>2</sub> Nanoparticles. <i>Small</i> , 2015, 11, 6444-6456.	10.0	24
46	A novel integrated thin film capacitor realized by a multilayer ceramic electrode sandwich structure. <i>Journal of the European Ceramic Society</i> , 1999, 19, 1413-1415.	5.7	23
47	Electrical conductivity and segregation effects of doped SrTiO <sub>3</sub> thin films. <i>Journal of the European Ceramic Society</i> , 2001, 21, 1673-1676.	5.7	23
48	Liquid Injection Atomic Layer Deposition of Crystalline TiO <sub>2</sub> Thin Films with a Smooth Morphology from Ti(O-i-Pr) <sub>2</sub> (DPM) <sub>2</sub> . <i>Journal of the Electrochemical Society</i> , 2009, 156, D296.	2.9	23
49	[Zr(NEtMe) <sub>2</sub> (guan-NEtMe) <sub>2</sub> ] as a Novel Atomic Layer Deposition Precursor: ZrO <sub>2</sub> Film Growth and Mechanistic Studies. <i>Chemistry of Materials</i> , 2013, 25, 3088-3095.	6.7	23
50	Structural and electrical properties of wet-chemically deposited Sr(Ti <sub>1-y</sub> Zr <sub>y</sub> )O <sub>3</sub> (y=0-1) thin films. <i>Integrated Ferroelectrics</i> , 1995, 10, 155-164.	0.7	22
51	KMC Simulation of the Electroforming, Set and Reset Processes in Redox-Based Resistive Switching Devices. <i>IEEE Nanotechnology Magazine</i> , 2018, 17, 1181-1188.	2.0	21
52	A SIMS study of cation and anion diffusion in tantalum oxide. <i>Physical Chemistry Chemical Physics</i> , 2018, 20, 989-996.	2.8	21
53	Nanostructured resistive memory cells based on 8-nm-thin TiO <sub>2</sub> films deposited by atomic layer deposition. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2011, 29, 01AD01.	1.2	20
54	Impedance spectroscopy study of the unipolar and bipolar resistive switching states of atomic layer deposited polycrystalline ZrO <sub>2</sub> thin films. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2015, 212, 751-766.	1.8	20

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55	Role of the Electrode Material on the RESET Limitation in Oxide ReRAM Devices. <i>Advanced Electronic Materials</i> , 2018, 4, 1700243.	5.1	20
56	Comprehensive model for the electronic transport in $\text{Pt/SrTiO}_3$ analog memristive devices. <i>Physical Review B</i> , 2020, 102, .	3.2	20
57	Liquid-Injection Atomic Layer Deposition of $\text{TiO}_x$ and $\text{PbTiO}_3$ Films. <i>Journal of the Electrochemical Society</i> , 2006, 153, F199.	2.9	18
58	Liquid Injection Atomic Layer Deposition of $\text{TiO}_x$ Films Using $\text{Ti}[\text{OCH}(\text{CH}_3)]_2$ . <i>Journal of the Electrochemical Society</i> , 2007, 154, G134.	2.9	18
59	Tuning the Performance of $\text{Pt/HfO}_2/\text{Ti/Pt}$ ReRAM Devices Obtained from Plasma-Enhanced Atomic Layer Deposition for $\text{HfO}_2$ Thin Films. <i>ECS Transactions</i> , 2016, 75, 177-184.	0.5	18
60	Resistance switching behavior of atomic layer deposited $\text{SrTiO}_3$ film through possible formation of $\text{Sr}_2\text{Ti}_6\text{O}_{13}$ or $\text{SrTi}_{11}\text{O}_{20}$ phases. <i>Scientific Reports</i> , 2016, 6, 20550.	3.3	17
61	Polar grain boundaries in undoped $\text{SrTiO}_3$ ceramics. <i>Journal of the European Ceramic Society</i> , 2001, 21, 2681-2686.	5.7	16
62	Shift of Phase Transition Temperature in Strontium Titanate Thin Films. <i>Integrated Ferroelectrics</i> , 2003, 58, 1371-1379.	0.7	16
63	Morphology and electrical properties of $\text{SrTiO}_3$ -films on conductive oxide films. <i>Journal of the European Ceramic Society</i> , 2001, 21, 1597-1600.	5.7	15
64	Study of atomic layer deposited $\text{ZrO}_2$ and $\text{ZrO}_2/\text{TiO}_2$ films for resistive switching application. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2014, 211, 301-309.	1.8	15
65	Intrinsic RESET Speed Limit of Valence Change Memories. <i>ACS Applied Electronic Materials</i> , 2021, 3, 5563-5572.	4.3	15
66	Influence of crystallization kinetics on texture of sol-gel PZT and BST thin films. <i>Journal of the European Ceramic Society</i> , 1999, 19, 1391-1395.	5.7	14
67	High Growth Rate in Atomic Layer Deposition of $\text{TiO}_2$ thin films by UV Irradiation. <i>Electrochemical and Solid-State Letters</i> , 2011, 14, H146.	2.2	14
68	Atomic Layer Deposition of $\text{TiO}_2/\text{Al}_2\text{O}_3$ Bilayer Structures for Resistive Switching Memory Applications. <i>Chemical Vapor Deposition</i> , 2014, 20, 282-290.	1.3	14
69	Forming-free metal-oxide ReRAM by oxygen ion implantation process. , 2016, , .		13
70	Internal Cell Resistance as the Origin of Abrupt Reset Behavior in $\text{HfO}_2$ -Based Devices Determined from Current Compliance Series. , 2016, , .		13
71	Evolution of short-range order in chemically and physically grown thin film bilayer structures for electronic applications. <i>Nanoscale</i> , 2020, 12, 13103-13112.	5.6	13
72	Mobility Modulation and Suppression of Defect Formation in Two-Dimensional Electron Systems by Charge-Transfer Management. <i>ACS Applied Materials &amp; Interfaces</i> , 2017, 9, 10888-10896.	8.0	12

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73	Impact of composition and crystallization behavior of atomic layer deposited strontium titanate films on the resistive switching of Pt/STO/TiN devices. Journal of Applied Physics, 2014, 116, 064503.	2.5	11
74	Influence of stoichiometry on the performance of MIM capacitors from plasma-assisted ALD Sr <sub>x</sub> Ti <sub>y</sub> O <sub>z</sub> films. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 389-396.	1.8	10
75	Design rules for threshold switches based on a field triggered thermal runaway mechanism. Journal of Computational Electronics, 2017, 16, 1175-1185.	2.5	10
76	Electroforming of Fe:STO samples for resistive switching made visible by electrocoloration observed by high resolution optical microscopy. Materials Research Society Symposia Proceedings, 2014, 1691, 31.	0.1	9
77	The influence of non-stoichiometry on the switching kinetics of strontium-titanate ReRAM devices. Journal of Applied Physics, 2016, 120, .	2.5	9
78	Far infrared and Raman spectroscopy of ferroelectric soft mode in SrTiO <sub>3</sub> thin films and ceramics. Integrated Ferroelectrics, 2001, 32, 11-20.	0.7	8
79	The importance of singly charged oxygen vacancies for electrical conduction in monoclinic HfO <sub>2</sub> . Journal of Applied Physics, 2021, 129, .	2.5	8
80	Review of Manufacturing Process Defects and Their Effects on Memristive Devices. Journal of Electronic Testing: Theory and Applications (JETTA), 2021, 37, 427-437.	1.2	8
81	Laserannealing studies of barium strontium titanate thin films using short laser pulses. Integrated Ferroelectrics, 2000, 30, 129-138.	0.7	7
82	High temperature conductivity behavior of doped SrTiO <sub>3</sub> thin films. Integrated Ferroelectrics, 2001, 33, 363-372.	0.7	7
83	Chemical deposition methods for ferroelectric thin films. Ferroelectrics, 2001, 259, 205-214.	0.6	7
84	Interface effects on memristive devices. , 2019, , 171-202.		7
85	Cation diffusion in polycrystalline thin films of monoclinic HfO <sub>2</sub> deposited by atomic layer deposition. APL Materials, 2020, 8, .	5.1	7
86	The effect of Zr on the microstructure of Ba(Ti <sub>1-y</sub> Zr <sub>y</sub> )O <sub>3</sub> thin films prepared by chemical-solution deposition. Materials Letters, 1998, 35, 375-379.	2.6	6
87	Energy dissipation during pulsed switching of strontium-titanate based resistive switching memory devices. , 2016, , .		6
88	Nanocrystalline Alkaline Earth Titanates and Their Conductivity Characteristics Under Changing Oxygen Ambients. Journal of Electroceramics, 2004, 13, 599-603.	2.0	5
89	Finite element simulations of interdigital electrode structures on high permittivity thin films. Integrated Ferroelectrics, 2001, 32, 63-72.	0.7	4
90	Liquid Injection Atomic Layer Deposition of Pb(Zr,Ti) <sub>3</sub> Thin Films on Three Dimensional Structures. Applications of Ferroelectrics, IEEE International Symposium on, 2007, , .	0.0	3

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91	Liquid Injection Atomic Layer Deposition of Metallic Ru Thin Films from Ru(tmhd) <sub>3</sub> and of High-k TiO <sub>2</sub> Thin Films from Ti(O-i-Pr) <sub>2</sub> (tmhd) <sub>2</sub> . ECS Transactions, 2009, 25, 289-298.	0.5	3
92	Simulation of threshold switching based on an electric field induced thermal runaway. , 2016, , .		3
93	Interfaces Formed by ALD Metal Oxide Growth on Metal Layers. ECS Transactions, 2017, 80, 87-95.	0.5	3
94	Defects in alkaline earth titanate thin films - the conduction behavior of doped BST. Integrated Ferroelectrics, 2001, 38, 229-237.	0.7	2
95	Liquid injection atomic layer deposition of perovskite-type multi-component oxide thin films for ferroelectric and higher-k three dimensional capacitor structures. , 2008, , .		2
96	(Invited) ALD Grown Functional Oxide Layers for Nonvolatile Resistive Switching Memory Applications. ECS Transactions, 2013, 50, 9-14.	0.5	2
97	FeRAM. , 2014, , 149-171.		2
98	Characterization of BaTiO <sub>3</sub> –BaZrO <sub>3</sub> Solid Solution Thin Films Prepared by MOCVD. Integrated Ferroelectrics, 2003, 55, 795-805.	0.7	1
99	MOCVD GROWTH OF (Pb,Ba)(Zr,Ti)O <sub>3</sub> THIN FILMS FOR MEMORY APPLICATIONS. Integrated Ferroelectrics, 2005, 75, 225-233.	0.7	1
100	Overcoming the RESET Limitation in Tantalum Oxide-Based ReRAM Using an Oxygen-Blocking Layer. , 2017, , .		1
101	Characterization of BaTiO <sub>3</sub> –BaZrO <sub>3</sub> Solid Solution Thin Films Prepared by MOCVD. Integrated Ferroelectrics, 2003, 55, 795-805.	0.7	1
102	(Pb <sub>1-x</sub> Ba <sub>x</sub> )TiO <sub>3</sub> Thin Films Prepared by Liquid Delivery MOCVD: Influence of the Process Parameters on Film Formation and Electrical Properties. Ferroelectrics, 2002, 268, 143-148.	0.6	0
103	Ba substituted Pb(ZrxTi1-x)O <sub>3</sub> thin films grown by MOCVD. Materials Research Society Symposia Proceedings, 2005, 902, 1.	0.1	0
104	Characterization of HfO <sub>2</sub> /TiO <sub>x</sub> ReRAM Cells in Pulse Operation Mode. , 2018, , .		0
105	Orientation and Microstructure Design. , 2013, , 407-429.		0
106	(Invited) Tuning the Switching Behavior of Nano-Crossbar Reram Devices By Design and Process Treatment of ALD Functional Oxide Layer Stacks. ECS Meeting Abstracts, 2017, , .	0.0	0
107	Two Stable Switching Modes with Opposite Polarity in Pt/TiO <sub>2</sub> /Ti Cells Based on Concurring Phenomena Close to the Pt/TiO <sub>2</sub> Interface. ECS Meeting Abstracts, 2017, , .	0.0	0
108	Interfaces Formed by ALD Metal Oxide Growth on Metal Layers. ECS Meeting Abstracts, 2017, , .	0.0	0

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109	Reliability Aspects of Memristive Devices for Computation-in-Memory Applications. , 2021, , .		0
110	NEUROTEC I: Neuro-inspired Artificial Intelligence Technologies for the Electronics of the Future. , 2022, , .		0